

SUBSTRATE PROCESSING APPARATUS, DETERMINATION METHOD, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE, AND PROGRAM

ABSTRACT

There is provided a technique that includes: a substrate processor processing a substrate; a gas supplier supplying, to the substrate processor, a gas that processes the substrate; an acquirer configured to perform the act of processing the substrate a predetermined number of times and acquire measurement values in a predetermined section during each act of processing the substrate; a determination condition setter configured to set a threshold for each of a plurality of predetermined determination items based on the measurement values acquired by the acquirer; and a determiner configured to, in the act of processing the substrate after the threshold is set, determine whether or not the acquired measurement values are within a range of the threshold for each of the plurality of predetermined determination items, and determine whether or not the act of processing the substrate is reproducible.

FIGS. 5A and 5B